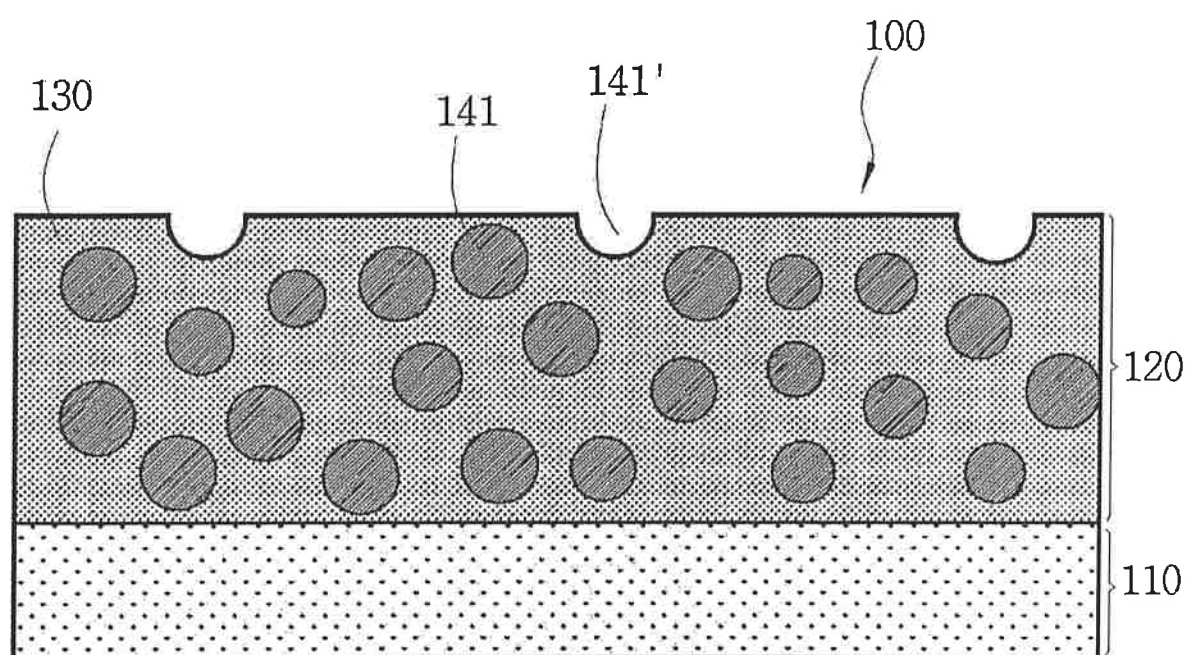
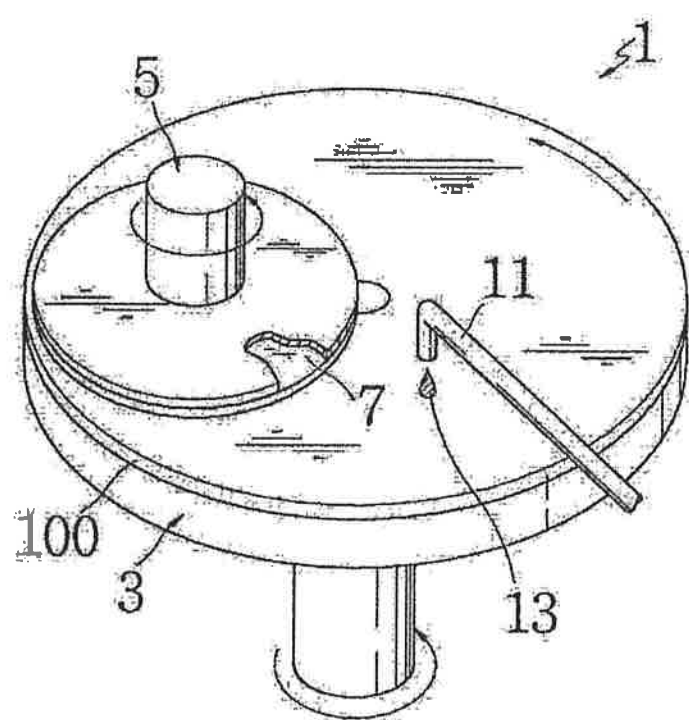


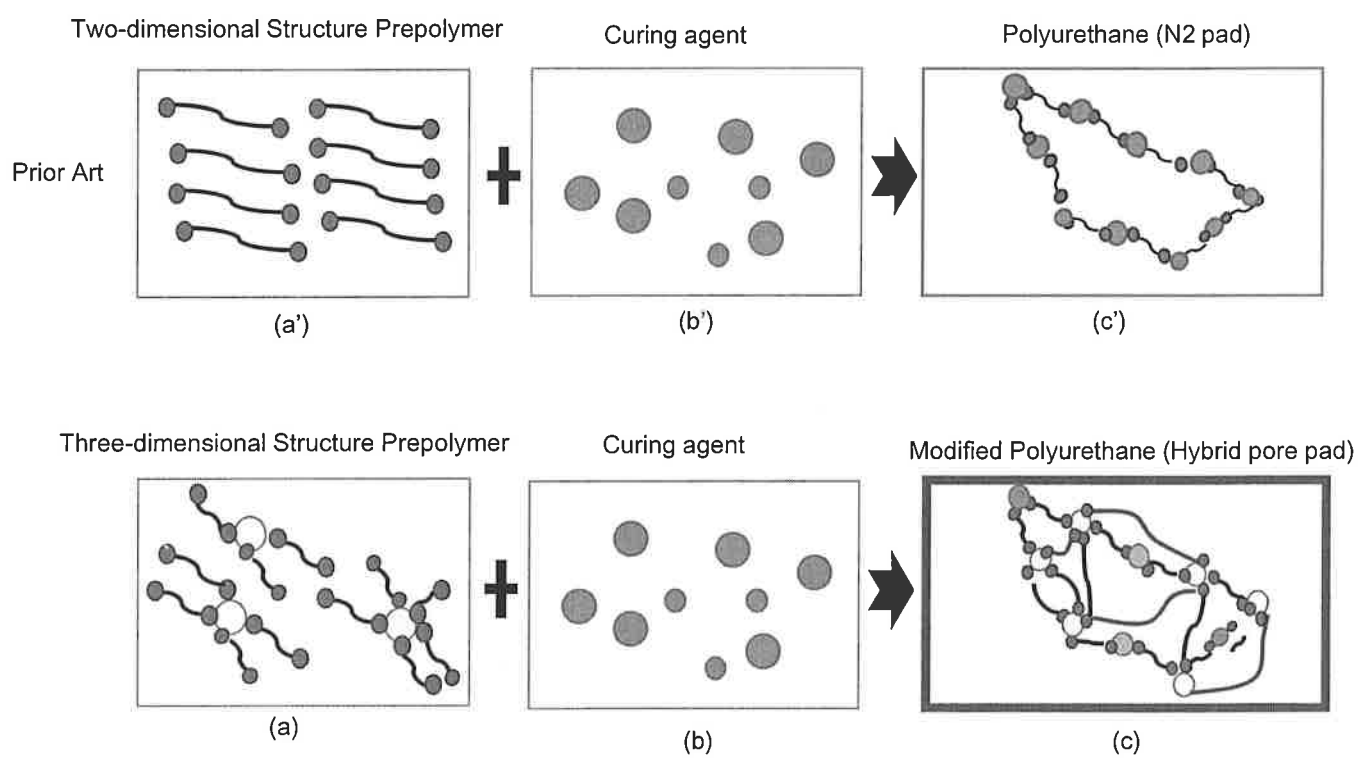
【Fig. 1】



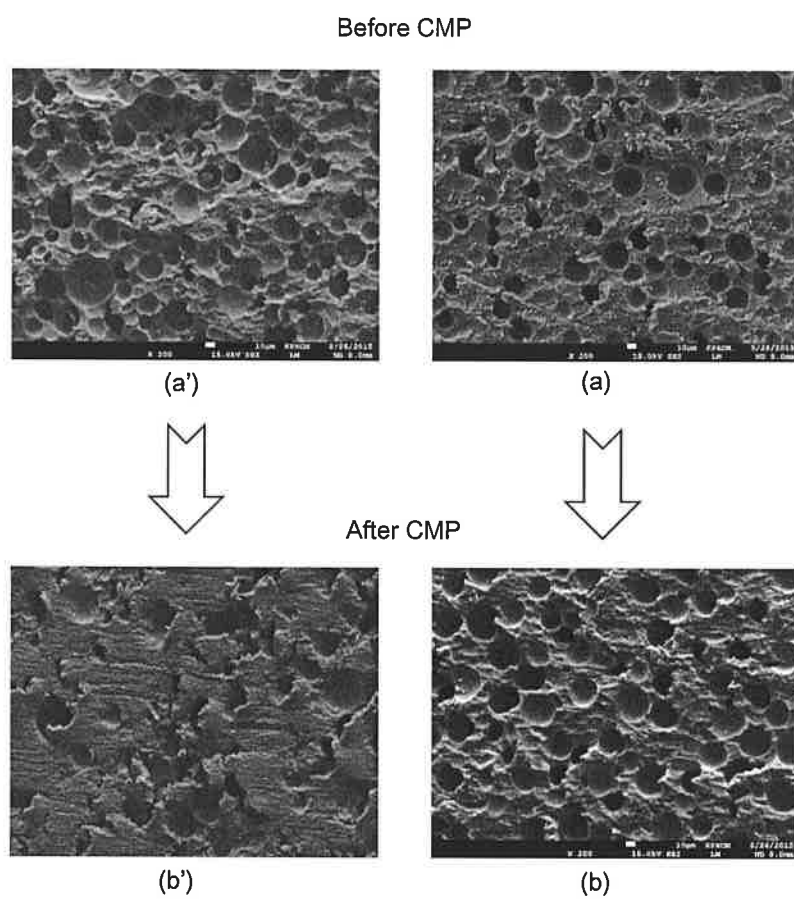
【Fig. 2】



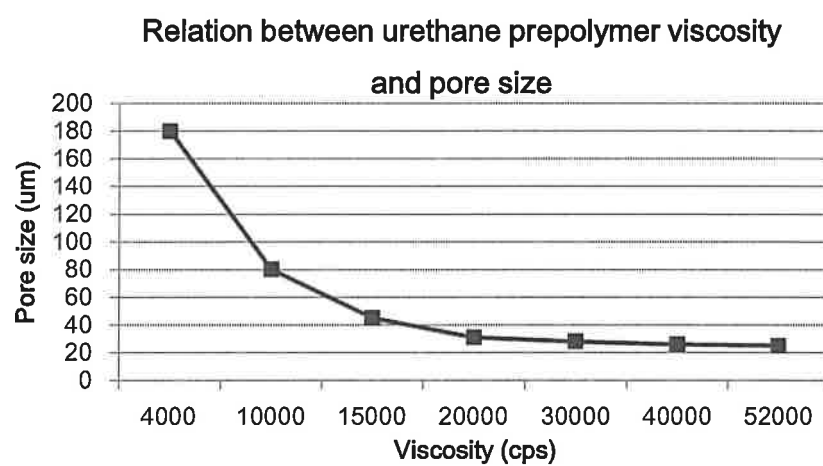
【Fig. 3】



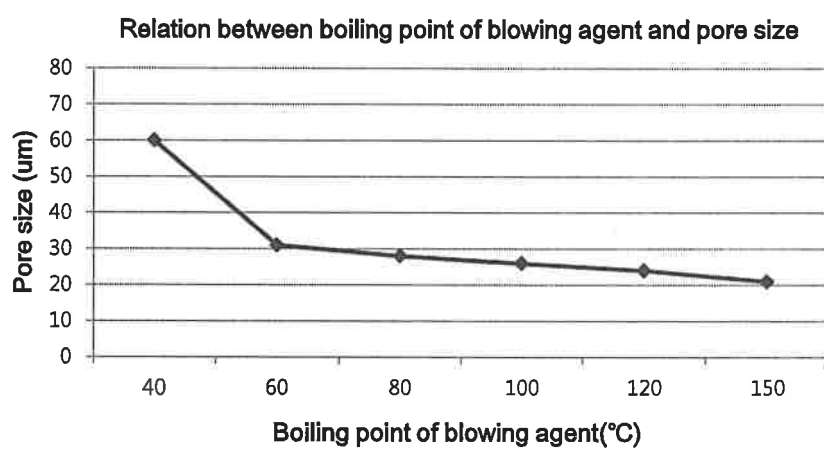
【Fig. 4】



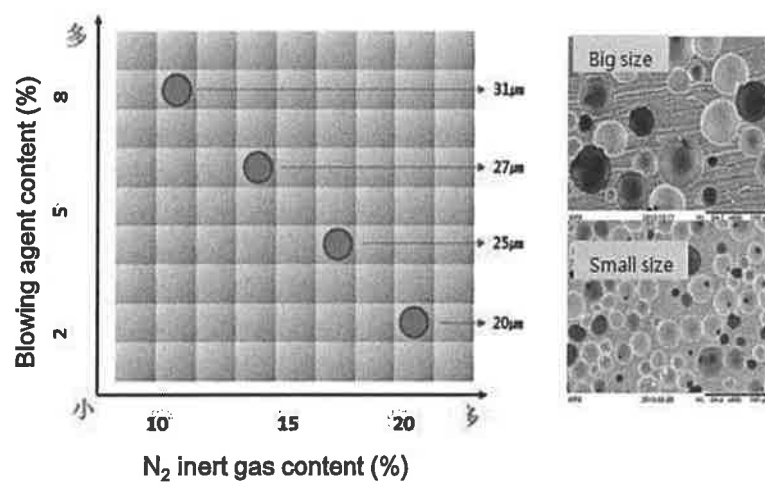
【Fig. 5】



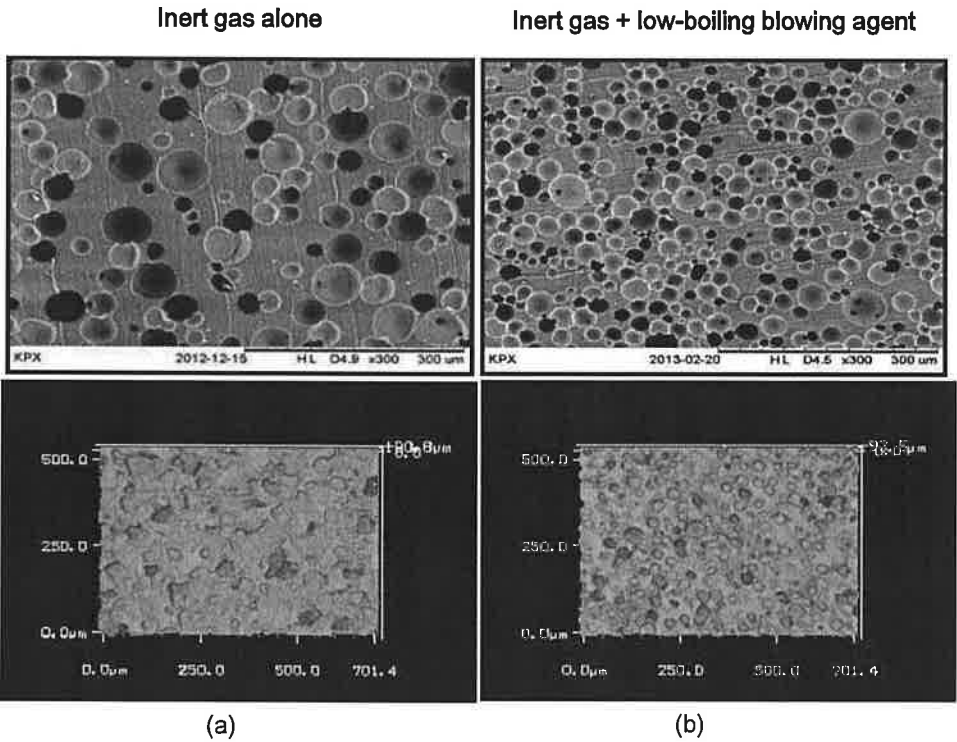
【Fig. 6】



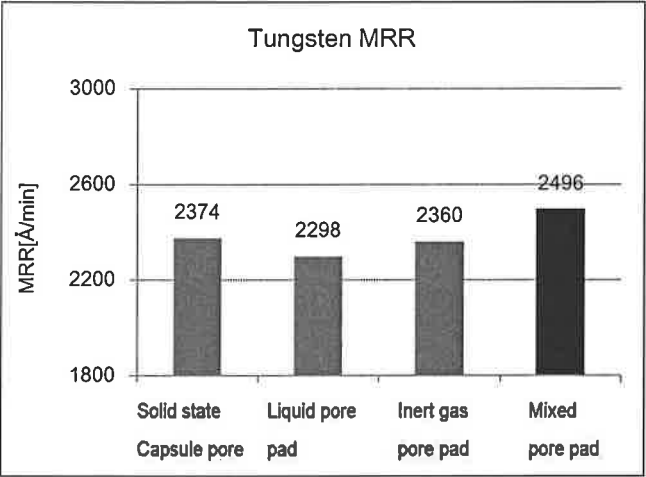
【Fig. 7】



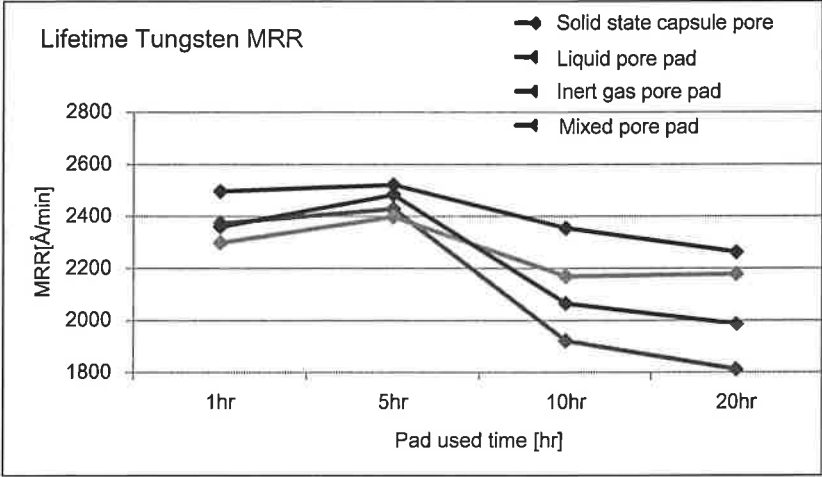
【Fig. 8】



【Fig. 9】



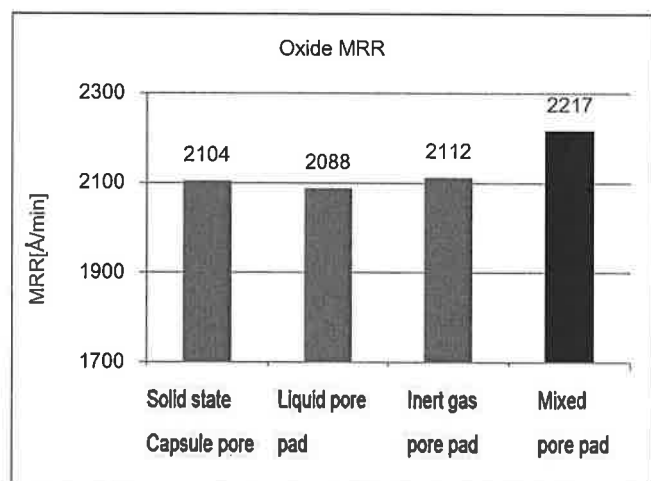
(a)



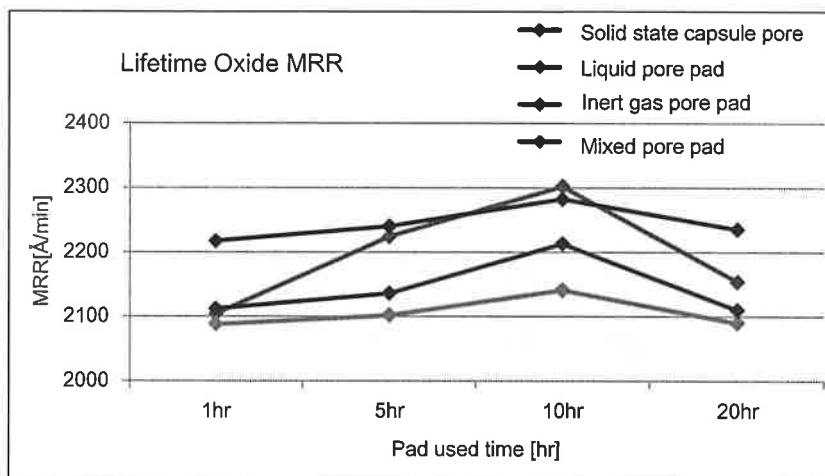
(b)

Apparatus	Wafer	Slurry	Disk
POLI-762	Tungsten	W	C1

【Fig. 10】



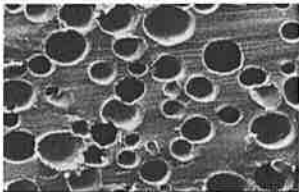
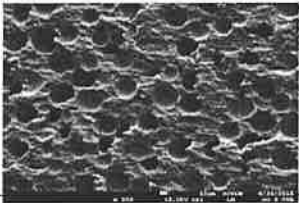
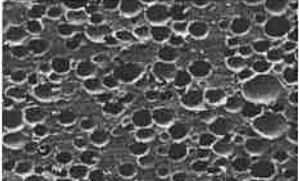
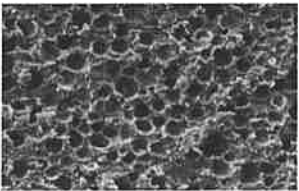
(a)



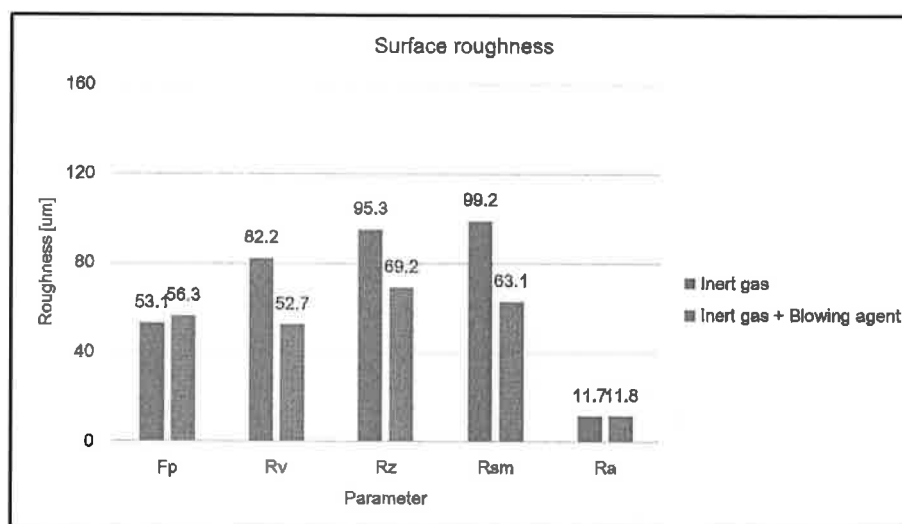
(b)

Apparatus	Wafer	Slurry	Disk
POLI-762	Oxide	T	C7

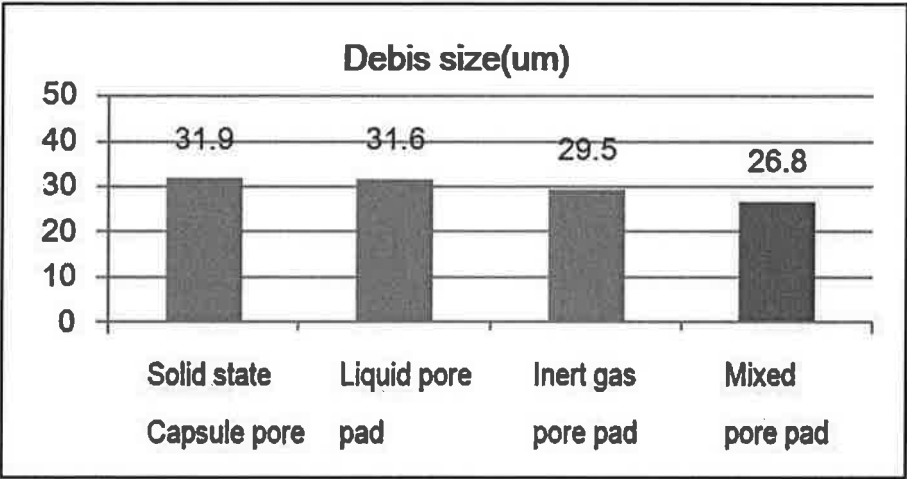
【Fig. 11】

Example 4	
Example 5	
Example 6	
Example 7	

【Fig. 12 (a)】



【Fig. 12 (b)】



【Fig. 12 (c)】

